# Constellation X-RayMission

## Properties of Vapor-Deposited Au:Er Films for Metallic Magnetic Calorimeters



H. Eguchi<sup>a</sup>, R. Bruni<sup>b</sup>, Y. H. Huang<sup>a</sup>, A. N. Mocharnuk-Macchia<sup>a</sup>, S. Romaine<sup>b</sup>, G. M. Seidel<sup>a</sup>, B. Sethumadhavan<sup>a</sup> and W. Yao<sup>a</sup>



<sup>a</sup> Department of Physics, Brown University, Providence, RI 02912 USA b Harvard-Smithsonian Center for Astrophysics, Cambridge, MA 02138 USA

#### **Constellation-X Mission**

High energy resolution x-ray spectroscopy with a microcalorimeter will start a new era for x-ray astronomy.

Science goals are to study:

- Effects of strong gravity in the vicinity of black holes
- Origin and evolution of supermassive black holes
- Dark Energy and dark matter
- Life cycles of matter

To achieve these goals, requirements for an x-ray detector are:

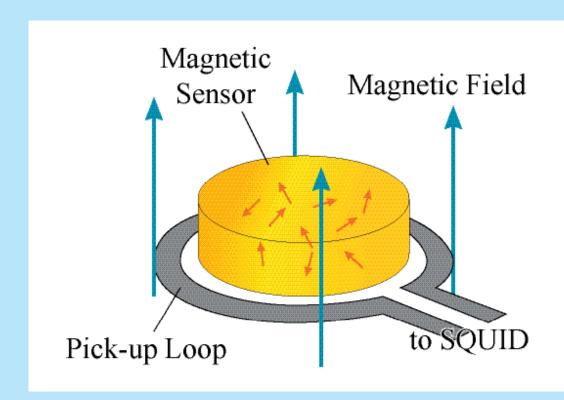
- $\Delta E_{EWHM}$  < 4 eV resolution at 6 keV
- Large focal-plane arrays of detectors (32 x 32 pixels)

## Metallic Magnetic Calorimeters (MMCs)

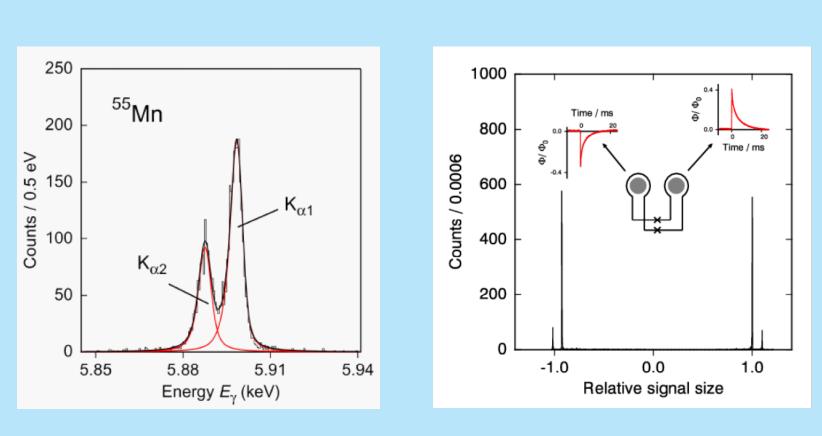
#### Detection Principle

- Paramagnetic sensor diluted in a nonmagnetic metal: Au:Er
- Change in magnetization due to temperature rise in sensor is detected by a SQUID.

$$\delta\Phi\propto rac{V}{r}rac{\partial M}{\partial T}rac{\delta E}{C_{
m total}}$$



Energy resolution  $\Delta E_{\text{FWHM}} = 3.4 \text{ eV}$ 



Two-pixel detector; Au:Er sensors and Au absorbers are manually assembled on SQUID chip

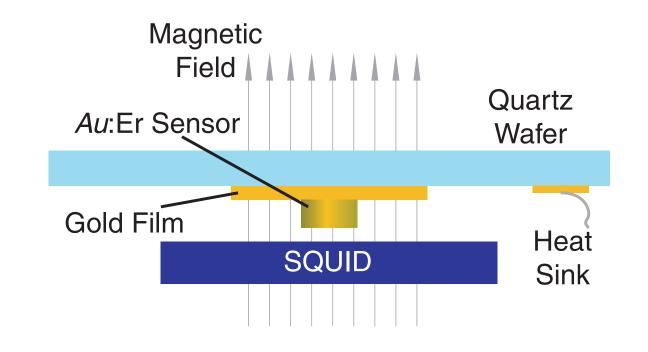
(Fleischmann et al., Nucl. Instr. and Meth. A 520 (2004) 27)

Magnetization of Sputtered Au:Er Film

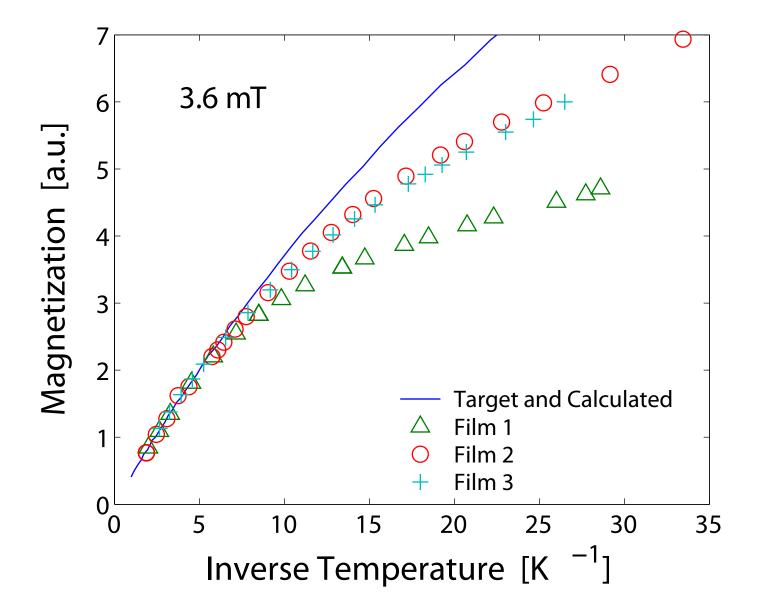
### High Temperatures

- SQUID magnetometer was used to measure magnetic moments of the target material and the sputtered films.
- Target has 1390 ppm Er concentration determined from the fit.
- Film 1 has 20% higher Er concentration than the target.
- Film 2 and 3 have the same Er concentration as the target.

## Low Temperatures



Below 200 mK the magnetization of the target material agreed with the mean field calculation of the magnetization for 1400 ppm natural Er, but



that of the sputtered films deviated in such a way that the change in magnetization with respect to temperature is less than predicted. The implication of this is that there is a larger exchange interaction in the films than exists between the randomly distributed Er ions in the bulk material, as assumed in the mean field calculation.

## Microfabrication of MMCs

Fabrication of Au:Er Film

Au:Er film was deposited onto

photoresist-coated Si substrate

by DC magnetron sputtering.

The gold target was doped with

1400 ppm natural Er, prepared by

the Ames Laboratory. The sub-

strate was maintained at room

temperature during deposition.

The chamber was pumped down

Cathode Power

Low

High

High

Film 1

Film 2

Film 3

Photolithography + vapor-deposition technology can be used to fabricate arrays of MMCs

to  $\sim 10^{-7}$  torr before deposition. The films were lifted off

the substrate after deposition. Three Au:Er films were

14.8

36.7

Deposition Rate Thickness

μm

4.5

5.5

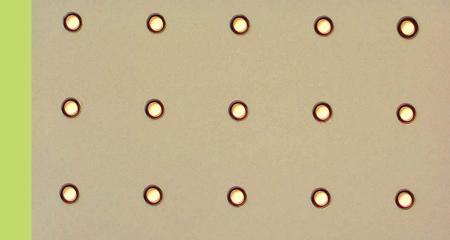
RRR

1.75

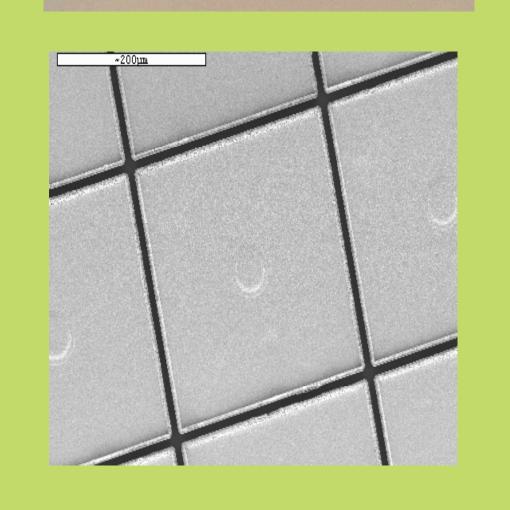
1.71

deposited under different sputtering conditions:

(Right) Au:Er sensor deposited in 50 um SQUID pickup loop



(Left) Array development for MMCs: sputtered sensor arrays



Thermal evaporation of Bi absorbers on top of sensor arrays deposited at GSFC (picture provided by Simon

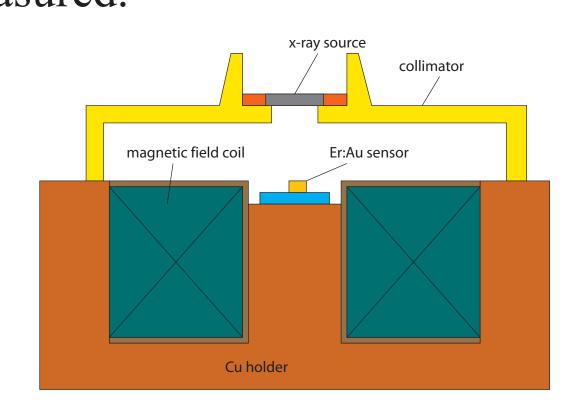
## Acknowledgement

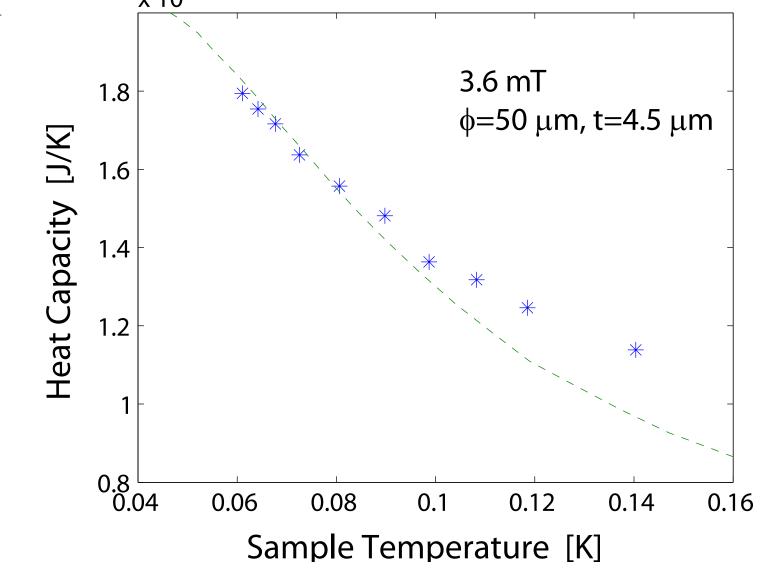
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Bandler)

## Heat Capacity Measurement

The heat capacity of film 2, which showed the least deviation in magnetization at low temperatures, was measured.





O Film 2

Inverse Temperature  $[K^{-1}]$ 

Fit 1390ppm,  $\chi_{dia} = -2.26x10^{-5}$ 

The measured heat capacity agrees to within 10% with calculation. The calculation includes contributions from Zeeman, exchange, and hyperfine interactions from 23% abundant <sup>167</sup>Er isotope.

#### Discussion and Conclusion

The high-temperature magnetization of the sputtered films agrees well with the properties of the bulk target material. However, the deviation of the magnetization below 200 mK implies a somewhat enhanced exchange interaction in the sputtered films compared to the bulk. Two possible causes of the increased interactions are (1) The indirect exchange (RKKY) is larger in sputtered films than in the bulk (2) Er ions are not randomly distributed in the sputtered films but are more likely to be found closer to other Er ions. Sputtered films produced from a lower concentration of Er and isotopically enriched in <sup>166</sup>Er are being pursued to learn how to produce high quality vapor-deposited MMCs.